

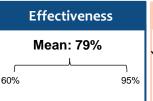
WETTING SYSTEM

Wetting systems humidify the process at the point of release (focusing on the emission source) to agglomerate and bind the fine particles to prevent dust from being dispersed into the workroom air. This control is not commonly used for engineered nanomaterials.

Three stages are defined when wettings systems could be used: before, during and after emissions.







Implementation

☐ Ready to use Development required

☐ Without any maintenance With regular maintenance

Cost

Mobile

€)



Target group

™ Workers

Consumer Environment



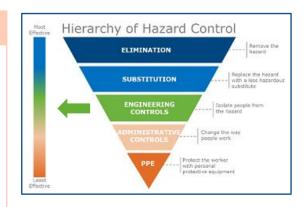


BRIEF DESCRIPTION OF THE SPECIFICATIONS

When moisture is added to the substance before the process in order to change the substance emission beginning potential, this is covered by another RMM not in the scope of this study.

Wetting at point of release: When moisture is added during the process at the point of release (like wet sawing or grinding) - it is considered to be a localized control. Although this is usually done to cool the saw blade or grinding wheel, it subsequently reduces airborne dust. This type of control is called "suppression at the point of release". Wetting systems can be applied in processes (e.g. transfer points) or hand-held tools (e.g. mobile wetting systems).

Knockdown suppression: When airborne contaminants are damped down or knocked down after they have been released into the work environment, this is called knockdown suppression (post generation suppression). This type of control is not commonly used and is far less effective than suppression at the point of release.



To know more

for the Advanced REACH Tool (ART)







